



IIT Bombay Nanofabrication Facility

Tool Name: ICPRIE - Dia

Training and Usage Policy

INDEX

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Contents

Training and Usage Policy :.....	1
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Training & Usage Policy:

- The tool category is semi clean A
- Allowed materials for etching are restricted to Si, SiN, SiO₂, SiC and Diamond for the initial time period.
- Only Photoresist is allowed as hard mask
- Other group IV materials need to be discussed with FIC for approval and usage.
- If the sample is processed from outside IITBNF (Completely/partially) the sample would be an external sample and would need contamination check as well as process approvals from FIC and Process Committee for usage in ICPRIE – Dia.
- Once in a month the tool will be blocked for the baseline of the tool.